

## Optical Lithography Patterning of DUV ma-N 2405

- 1) **Clean:** using Acetone and IPA and bake at 85°C for 15 minutes in an oven
- 2) **Spin Coat:** 3000 rpm, 30 s
- 3) **Pre-bake:** 100°C for 15 minutes in an oven
- 4) **Expose:** 3-20 minutes (using our MA6, the intensity was 8.8 mW/cm<sup>2</sup>)
  - Sample 1: 15 minutes
  - Sample 2: 10 minutes
  - Sample 3: 05 minutes
  - Sample 4: 03 minutes
  - Sample 5: 07 minutes
- 5) **Develop:** ma-D 525 developer for different times (45 s to 300 s) to change the undercut profile

**Result:** The sample with 5 minutes exposure looked good. All others were not good. The development time was different for different feature sizes and the smallest were developed at around 250 s.

